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UNITED STATES PATENT AND TRADEMARK OFFICE

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DATE MAILED: 02/20/2004

| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
|--|------------------------|----------------------|---------------------|------------------|
| 10/080,104 | 02/21/2002 | Kaoru Koike | 09792909-5344 | · 1692 |
| 26263 7 | 263 7590 02/20/2004 | | EXAMINER | |
| SONNENSC | HEIN NATH & ROS | ERDEM, FAZLI | | |
| P.O. BOX 061080 WACKER DRIVE STATION, SEARS TOWER | | | ART UNIT | PAPER NUMBER |
| | CHICAGO, IL 60606-1080 | | | |

Please find below and/or attached an Office communication concerning this application or proceeding.

PTO-90C (Rev. 10/03)

| | | Application No. | Applicant(s) | | |
|---|--|---|---|--|--|
| | | 10/080,104 | KOIKE ET AL. | | |
| | Office Action Summary | Examiner | Art Unit | | |
| | | Fazli Erdem | 2826 | | |
| Period fo | The MAILING DATE of this communication app or Reply | ars on the cover sheet with the c | orrespondence address | | |
| THE - Exte after - If the - If NC - Failu Any | ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. In period for reply specified above is less than thirty (30) days, a reply operiod for reply is specified above, the maximum statutory period for reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b). | 36(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE | ely filed s will be considered timely. the mailing date of this communication. O (35 U.S.C. § 133). | | |
| Status | | | | | |
| 1) | Responsive to communication(s) filed on <u>Electron</u> | ion response filed on 11/13/2003 | | | |
| 2a)□ | This action is FINAL . 2b)⊠ This action is non-final. | | | | |
| 3)□ | Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213. | | | | |
| Disposit | ion of Claims | | | | |
| 5)⊠ 6)⊠ 7)⊠ | ✓ Claim(s) 1-86 is/are pending in the application. 4a) Of the above claim(s) 1-11 and 38-49 is/are withdrawn from consideration. ✓ Claim(s) 28-37 and 50-86 is/are allowed. ✓ Claim(s) 12 and 14-16 is/are rejected. ✓ Claim(s) 13 and 17-27 is/are objected to. ✓ Claim(s) are subject to restriction and/or election requirement. | | | | |
| Applicat | ion Papers | | | | |
| 10) | The specification is objected to by the Examine The drawing(s) filed on is/are: a) access Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex | epted or b) objected to by the Edrawing(s) be held in abeyance. See ion is required if the drawing(s) is obj | e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d). | | |
| Priority (| ınder 35 U.S.C. § 119 | | | | |
| a)l | Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau See the attached detailed Office action for a list of | s have been received. s have been received in Application ity documents have been receive I (PCT Rule 17.2(a)). | on No d in this National Stage | | |
| Attachmen | t(s) e of References Cited (PTO-892) | 4) 🔲 Interview Summary | (PTO-413) | | |
| 2) Notic | e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date | Paper No(s)/Mail Da | | | |

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DETAILED ACTION

Allowable Subject Matter

- 1. Claims 28-37 and 50-86 allowed.
- 2. Claims 13 and 17-27 objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 12, 14-16 rejected under 35 U.S.C. 103(a) as being unpatentable over Mizutani et al. (6,641,962) in view of Nishi et al. (5,464,715) further in view of Torigoe (5,231,471) further in view of Matsumoto et al. (6,151,120) further in view of Saiki et al. (5,715,037).

Regarding Claims 12, 14-16, Mizutani et al. disclose micro devices manufacturing method utilizing concave and convex alignment mark patterns where an exposure method includes a first step of forming on a substrate an alignment mark including a concave and convex pattern, a second step of forming a coat over the alignment mark and the other area on the substrate, a third step of flatting the coat and a fourth step of applying a photosensitive material on the coat flattened by the third step and projecting a mask pattern. Mizutani et al. fail to disclose the required pattern structure, pattern structure in the proper configuration,

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support/holding structure and the support/holding structure in the required manner. However, Nishi et al. disclose a method of driving a mask stage and method of mask alignment where the required pattern structure is disclosed. Furthermore, Torigoe discloses an alignment and exposure apparatus where the required pattern structure in the required configuration is disclosed. Matsumoto et al. disclose an exposure apparatus and method where the required support/holding structure is disclosed. Finally, Saiki et al. disclose a scanning exposure apparatus where the required support/holding structure in the required manner is disclosed.

It would have been obvious to one of having ordinary skill in the art at the time the invention was made to include the required pattern, required pattern structure in the required configuration, required support/holding structure and the required support/holding structure in the required configuration in Mizutani et al. as taught by Nishi et al., Torrigoe, Matsumoto et al., and Saiki et al. respectively in order to have a semiconductor-making apparatus with higher performance.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fazli Erdem whose telephone number is (703) 305-3868. The examiner can normally be reached on M - F 8:00 - 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan Flynn can be reached on (703) 308-6601. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Starting February 4, 2004, Examiner Fazli Erdem's phone number will be changed to

(571) 272-1914 and his SPE Nathan Flynn's phone number will be changed to (571) 272-1915

FE

February 7, 2004

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